

Notice of Allowability	Application No.	Applicant(s)
	10/703,387	DELOACH ET AL.
	Examiner	Art Unit
	Toniae M. Thomas	2822
The MAILING DATE of this communication appear All claims being allowable, PROSECUTION ON THE MERITS IS (herewith (or previously mailed), a Notice of Allowance (PTOL-85) of NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIC of the Office or upon petition by the applicant. See 37 CFR 1.313	OR REMAINS) CLOSED in this apport of the communication of the communication of the communication is subject to the communication in the communication is subject to the c	plication. If not included
1. X This communication is responsive to amendment filed on 0:	3 Jan 2005 and the interview with J	. Garner on 18 Feb. 2005 .
2. ☑ The allowed claim(s) is/are <u>1,2 and 5-9</u> .		
3. $igotimes$ The drawings filed on <u>06 November 2003</u> are accepted by t	he Examiner.	
4. Acknowledgment is made of a claim for foreign priority und a) All b) Some* c) None of the: 1. Certified copies of the priority documents have 2. Certified copies of the priority documents have 3. Copies of the certified copies of the priority documents have International Bureau (PCT Rule 17.2(a)). * Certified copies not received: Applicant has THREE MONTHS FROM THE "MAILING DATE" of noted below. Failure to timely comply will result in ABANDONMETHIS THREE-MONTH PERIOD IS NOT EXTENDABLE. 5. A SUBSTITUTE OATH OR DECLARATION must be submit INFORMAL PATENT APPLICATION (PTO-152) which gives (a) including changes required by the Notice of Draftsperson (b) hereto or 2) to Paper No./Mail Date (b) including changes required by the attached Examiner's Paper No./Mail Date Identifying Indicia such as the application number (see 37 CFR 1.8 each sheet. Replacement sheet(s) should be labeled as such in the content of the depose the content of the conten	been received. been received in Application No uments have been received in this of this communication to file a reply ENT of this application. Ited. Note the attached EXAMINER is reason(s) why the oath or declarate the submitted. On's Patent Drawing Review (PTO- Amendment / Comment or in the Comment or in the Comment of the drawing header according to 37 CFR 1.121(content).	national stage application from the complying with the requirements. 'S AMENDMENT or NOTICE OF stion is deficient. 948) attached Office action of the back) of d). must be submitted. Note the
attached Examiner's comment regarding REQUIREMENT F Attachment(s) 1. ☑ Notice of References Cited (PTO-892)	OR THE DEPOSIT OF BIOLOGICA	ratent Application (PTO-152)
2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948)	6. ☑ Interview Summary	
Information Disclosure Statements (PTO-1449 or PTO/SB/08 Paper No./Mail Date	Paper No./Mail Dat B), 7. ⊠ Examiner's Amendn	e nent/Comment
4. Examiner's Comment Regarding Requirement for Deposit	•	ent of Reasons for Allowance
of Biological Material	9. Other	- minuminimini.
		Mary Wilczewski Primary Examiner

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EXAMINER'S AMENDMENT

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1. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with Jacqueline Garner on 18 February 2005.

Amendment

2. The application has been amended as follows:

<u>In Cl</u>aims

Claims 10-12 and 15-18 have been canceled.

Reasons for Allowance

3. The following is an examiner's statement of reasons for allowance: although newly cited US Patent 6,040,231 to Wu discloses etching a portion of the substrate in addition to the pad layer during a first etching step, there is no teaching or suggestion in Wu to motivate one of ordinary skill in the art to etch a portion of the substrate in the known method of Choi. In Wu's method, the substrate is etched to provide a trench having top corners, which are subsequently processed to form an aslope periphery at these top corners (note figs. 2C, 2D, and 2E of Wu). Since the trench of Choi has vertical sidewalls extending from the top to the bottom surfaces of the trench, there is no motivation to etch a portion of the substrate in the known method of Choi.

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Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Toniae M. Thomas whose telephone number is (571) 272-1846. The examiner can normally be reached on Monday-Thursday from 8:30 a.m. to 5:30 p.m.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Amir Zarabian can be reached on (571) 272-1852. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

TMT

22 February 2005

Mary Wilczewski Primary Examiner